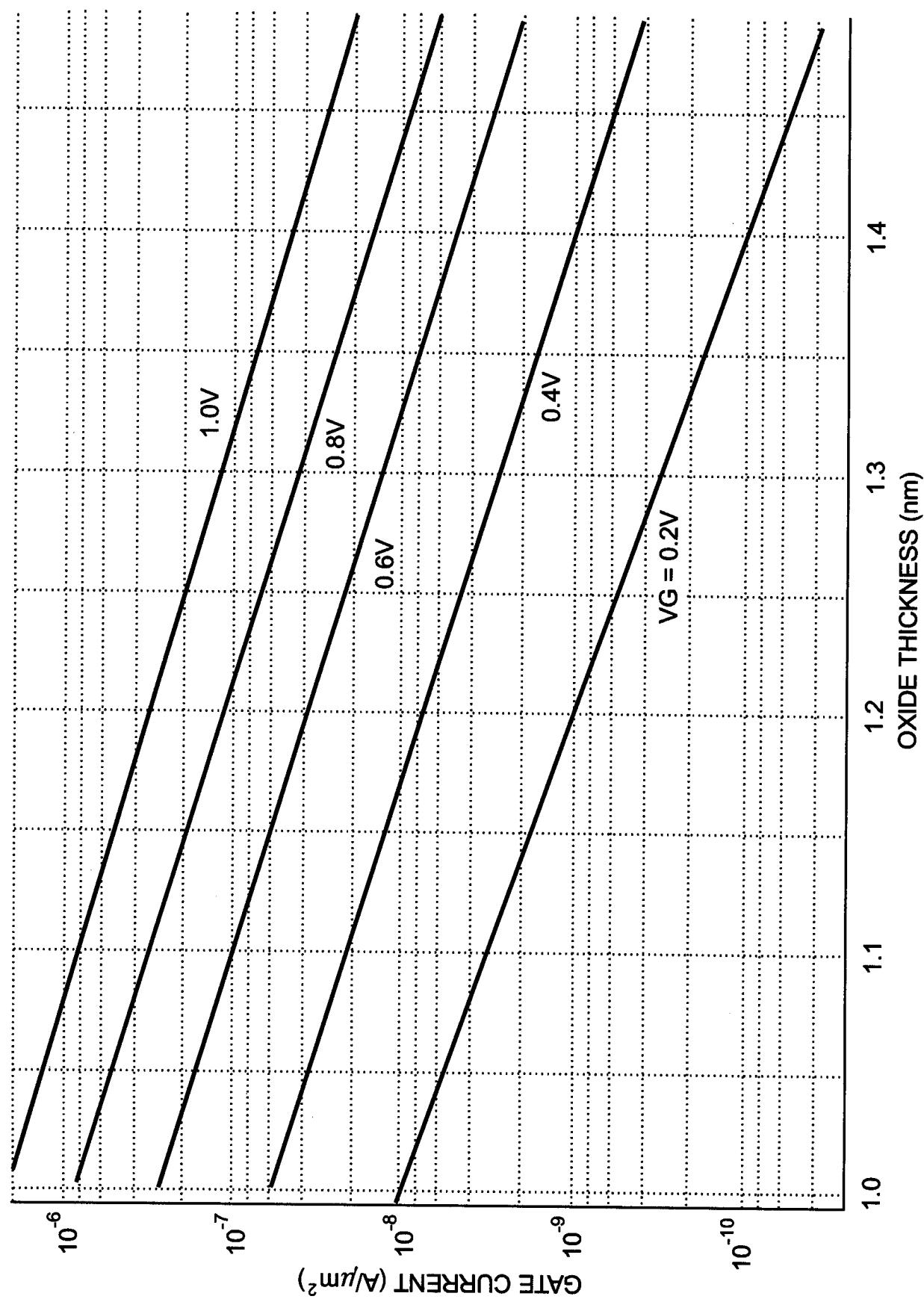
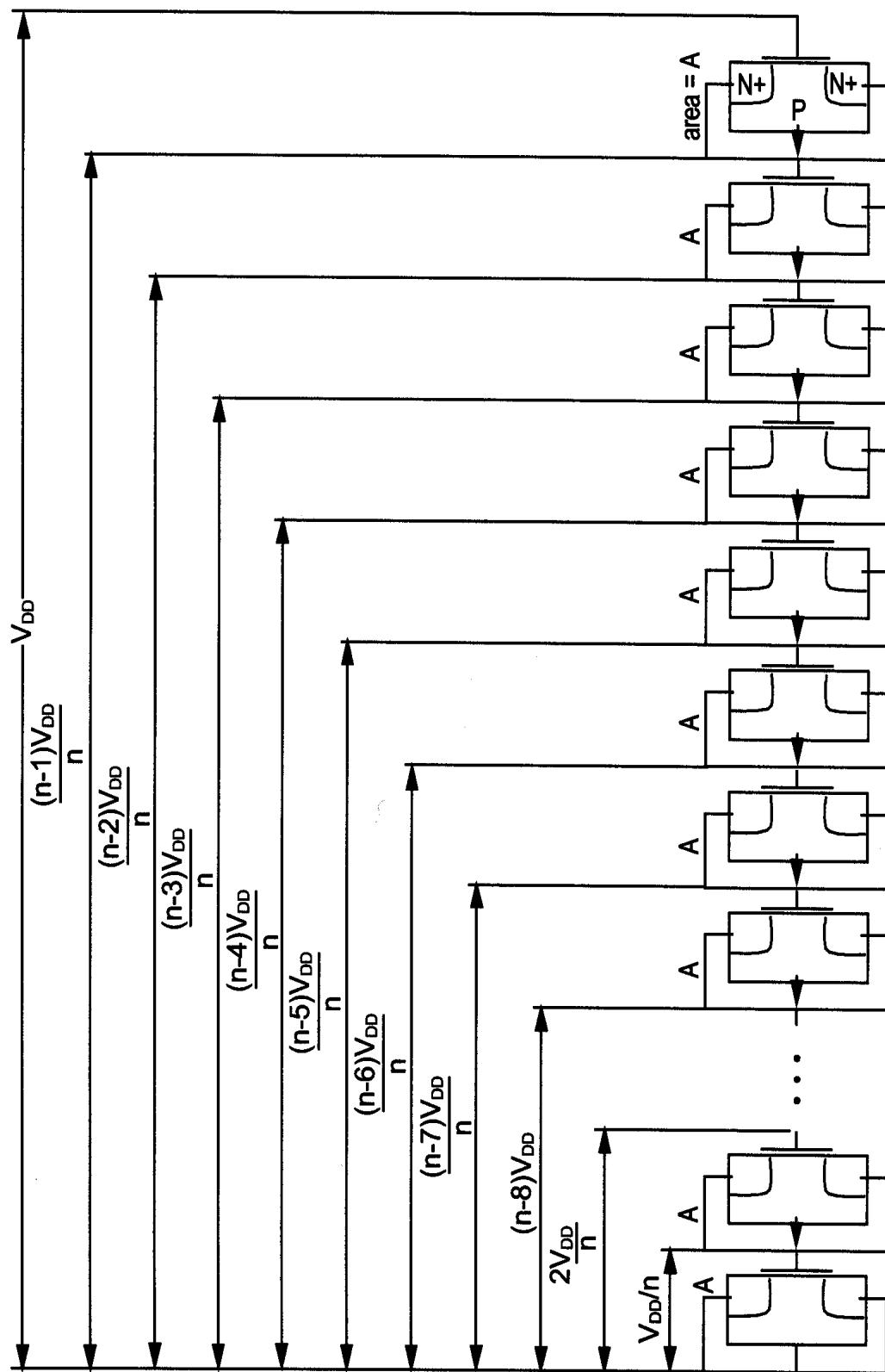


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FIG. 1
NFET GATE CURRENT VERSUS OXIDE THICKNESS

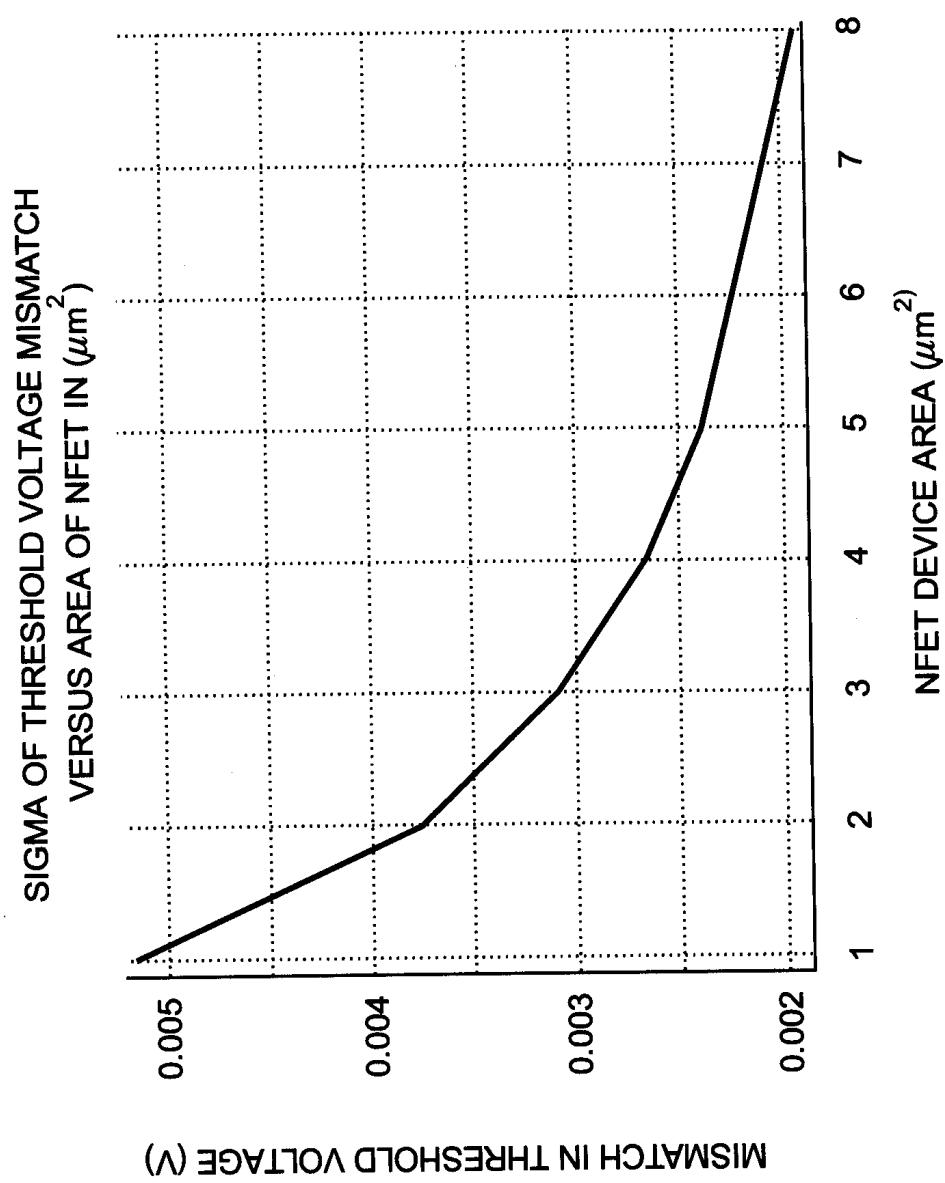
2/9

FIG. 2



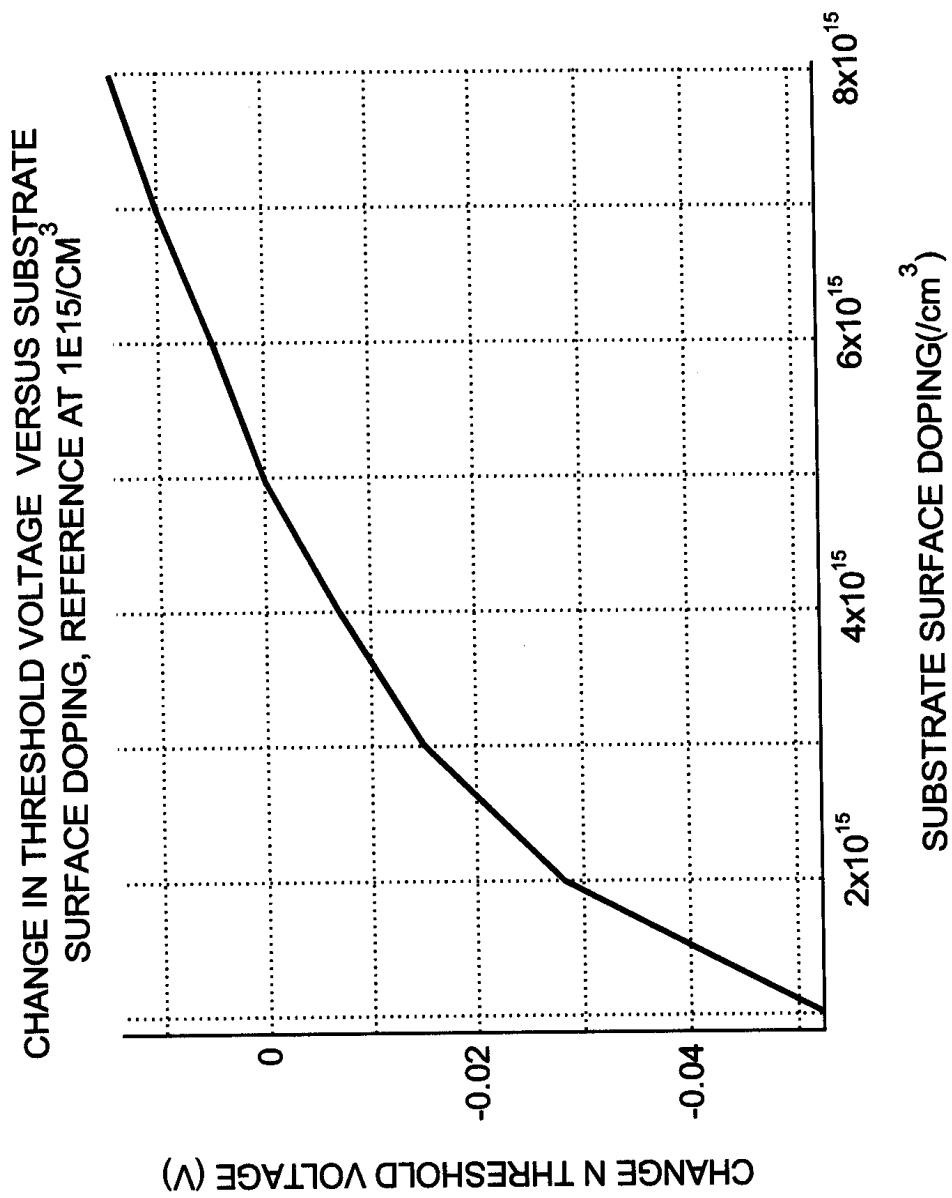
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FIG. 3



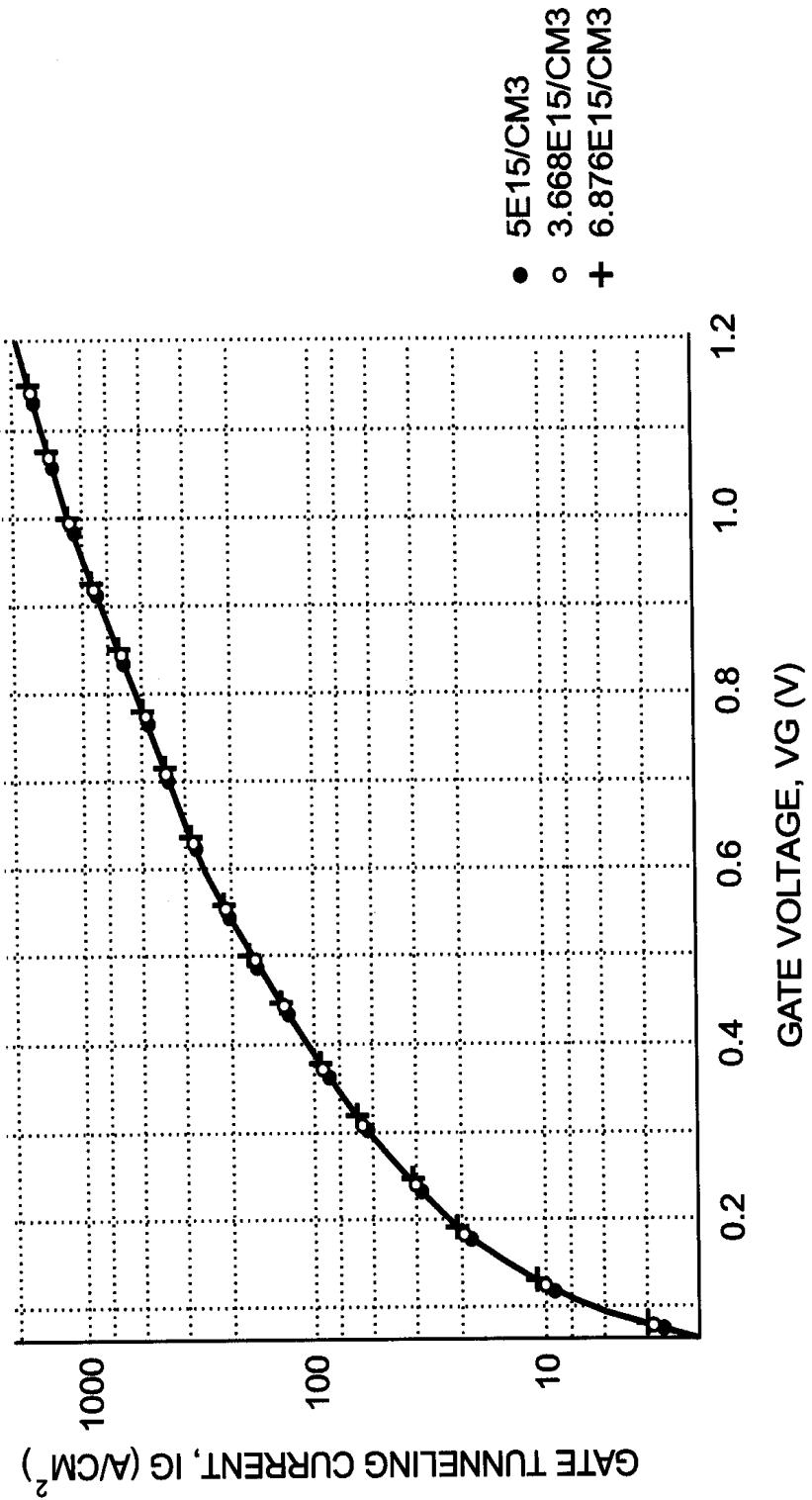
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FIG. 4



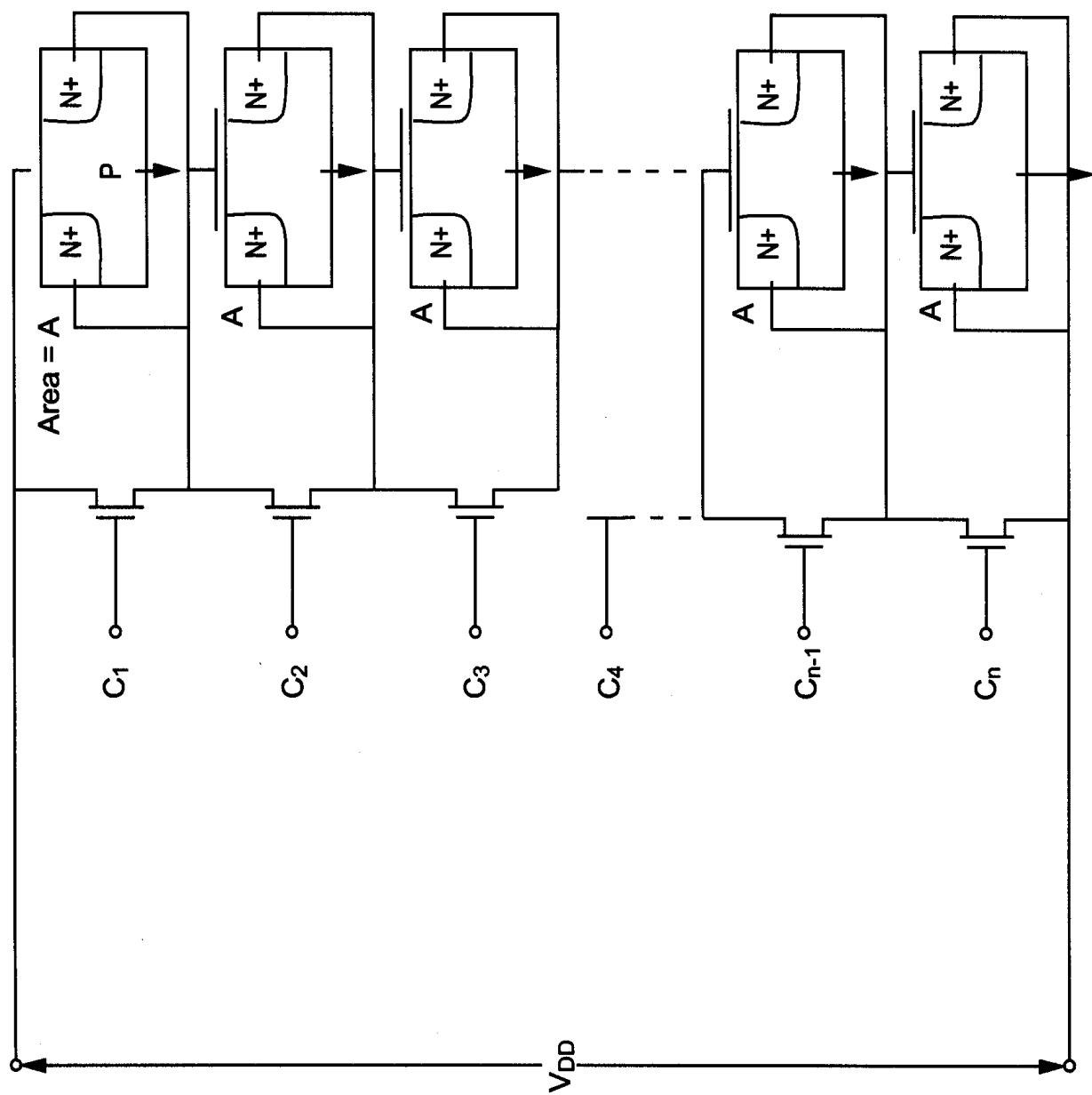
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FIG. 5

EFFECT OF SUBSTRATE SURFACE DOPING ON
NFET, GATE TUNNELING CURRENT

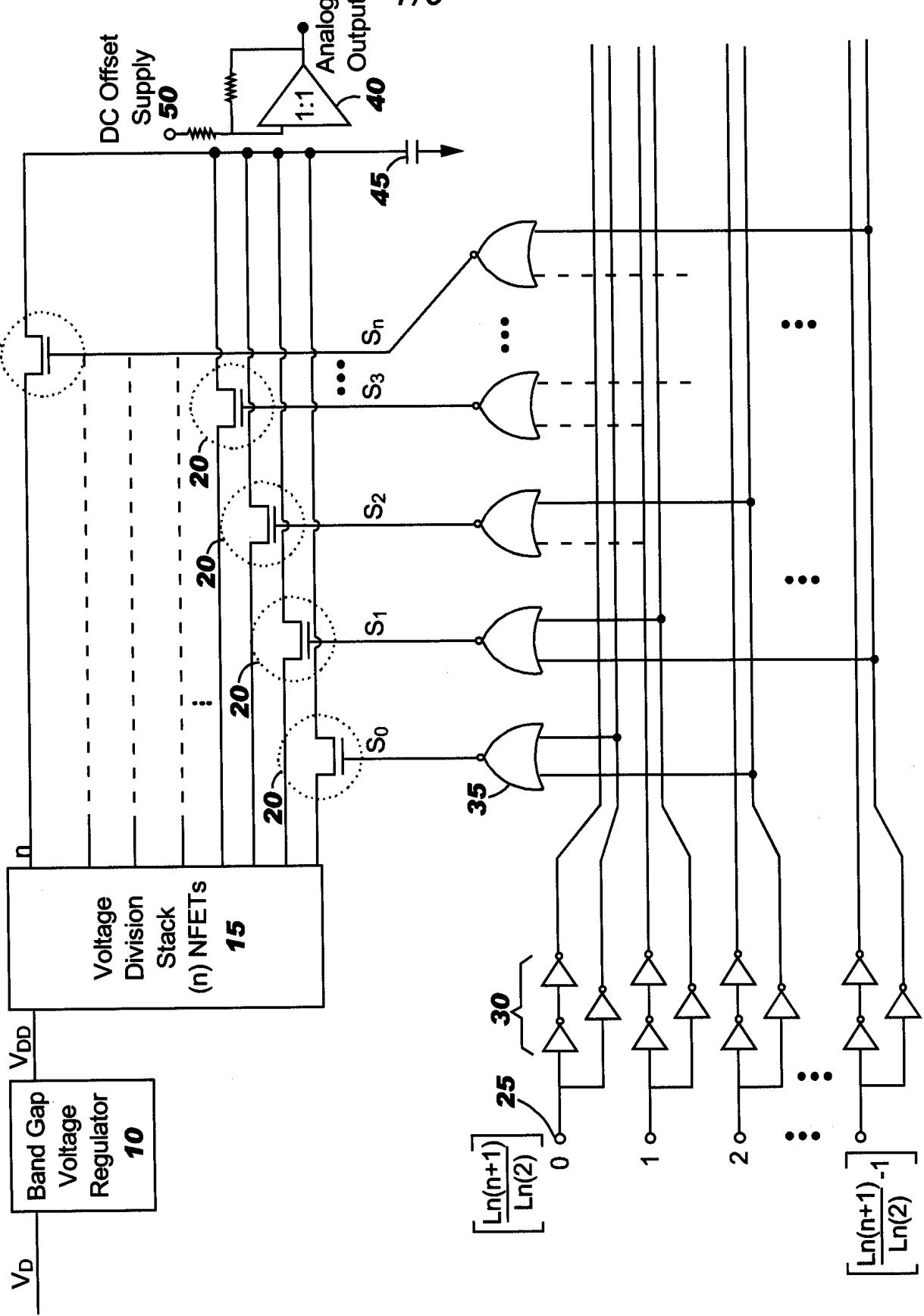
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FIG. 6



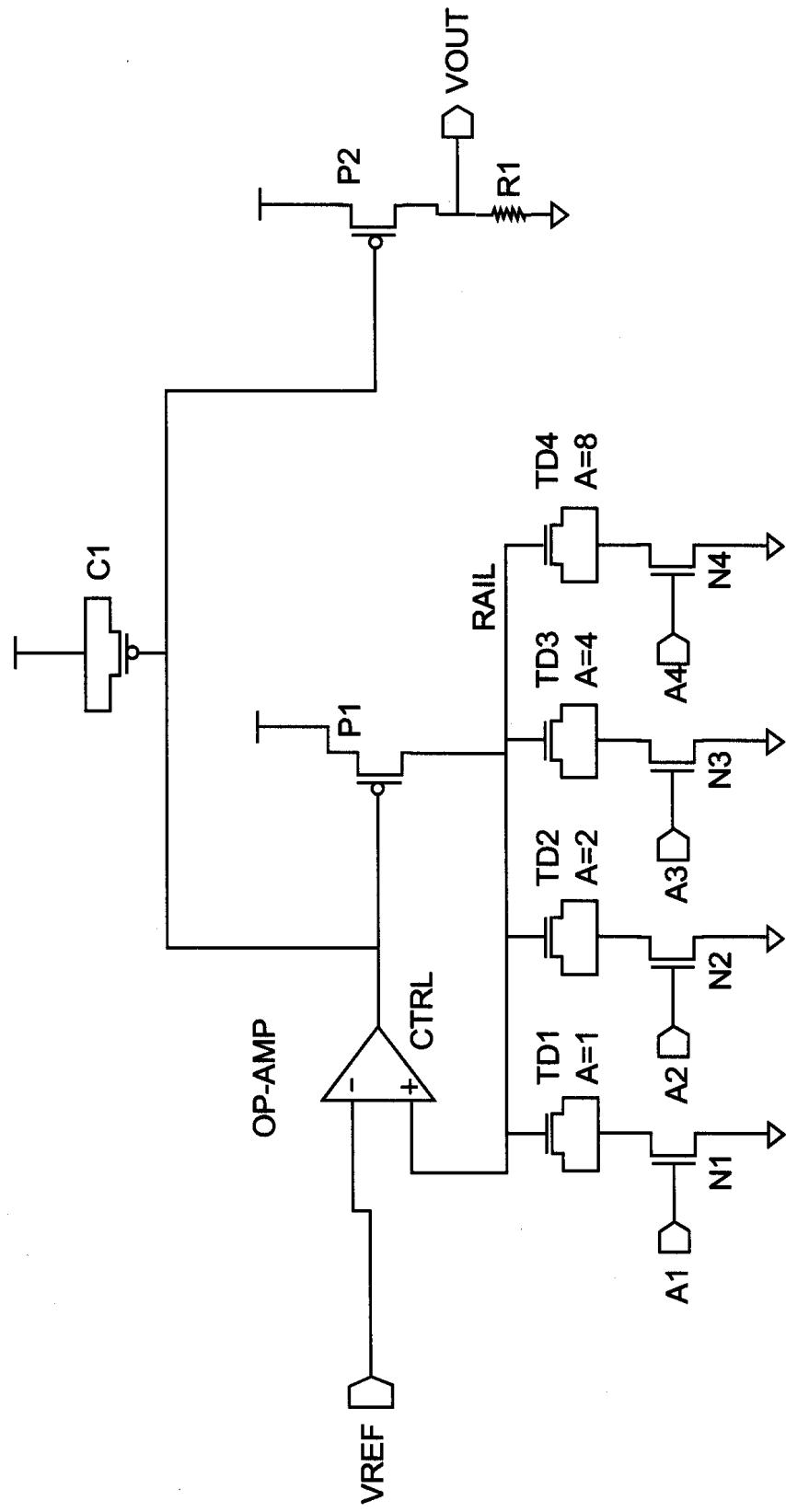
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FIG. 7



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FIG. 8



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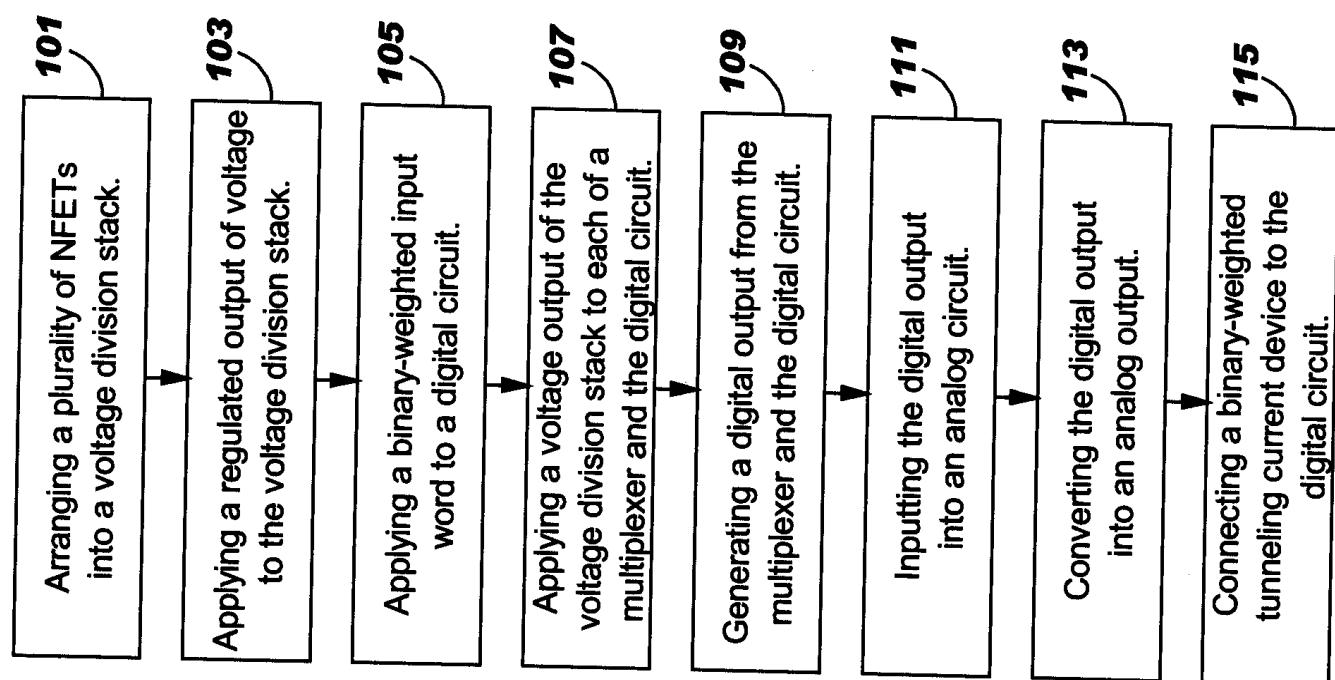


FIG. 9